



NOTES

1. COATING(S1): LOW GDD COATING  
 $R_s > 99\% @ 460 \text{ nm} - 590 \text{ nm}, \text{AOI} = 45^\circ$   
 $R_p > 99\% @ 480 \text{ nm} - 560 \text{ nm}, \text{AOI} = 45^\circ$
2. GDD:  
 $|GDD_s| < 30 \text{ fs}^2 @ 460 \text{ nm} - 590 \text{ nm}, \text{AOI} = 45^\circ$   
 $|GDD_p| < 30 \text{ fs}^2 @ 480 \text{ nm} - 560 \text{ nm}, \text{AOI} = 45^\circ$
3. CLEAR APERTURE(S1, S2):  $> 90\% \text{ CA}$
4. SURFACE QUALITY(S1, S2): 10/5(S/D)
5. SURFACE FLATNESS(S1):  $\lambda / 10 @ 633 \text{ nm}$
6. PARALLELISM(S1, S2):  $< 10 \text{ arcsec}$
7. CHAMFER: 0.1 mm,  $45^\circ$
8. THICKNESS TOLERANCE:  $\pm 0.1 \text{ mm}$
9. DIAMETER TOLERANCE:  $+0.0 \text{ mm} / -0.1 \text{ mm}$
10. BACK SURFACE(S2): POLISHED

DRAWING PROJECTION			<b>LBTEK</b>			
	NAME	DATE				
DRAWN	LZHOU	Aug./5th/24	ULTRAFAST MIRROR $\text{Ø} 25.4 \text{ mm} \times 6 \text{ mm}, 460 \text{ nm} - 590 \text{ nm}$			
APPROVAL	WCHENG	Aug./5th/24	MATERIAL	WEIGHT	SCALE	REV
FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES			UVFS	6.7 g	2:1	D